

IN THE CLAIMS:

The text of all pending claims, (including withdrawn claims) is set forth below. Cancelled and not entered claims are indicated with claim number and status only. The claims as listed below show added text with underlining and deleted text with ~~strikethrough~~. The status of each claim is indicated with one of (original), (currently amended), (cancelled), (withdrawn), (new), (previously presented), or (not entered).

Please CANCEL claims 12 and 13, without prejudice:

1. (PREVIOUSLY PRESENTED) A method of forming a rib pattern, having rib portions of relatively lower and higher heights, on a substrate of a plasma display panel, the method comprising:
 - forming a first material layer, having a thickness corresponding to the height of the lower height rib portions, on the substrate;
 - forming on the first material layer a first masking pattern defining the lower height rib portions;
 - superimposing on the first material layer a second material, a combined thickness of the first and second material layers being substantially equal to a height of the higher height rib portions;
 - forming on the second material layer a second masking pattern defining the higher height portions of the rib pattern; and
 - removing the portions of the first and second material layers, except for the lower and higher rib portions defined respectively by the second and first masking patterns.
2. (ORIGINAL) The method for forming a rib pattern as claimed in claim 1, wherein the removing the portions of the first and second material layers is a single process.
3. (ORIGINAL) The method for forming a rib pattern as claimed in claim 1, wherein said first material contains a white pigment.
4. (ORIGINAL) The method for forming a rib pattern as claimed in claim 1, wherein the rib portions of relatively higher heights comprise barrier rib portions.

5. (ORIGINAL) A method of forming a rib pattern, having rib portions of relatively lower and higher heights, on a substrate of a plasma display panel, said method comprising:

forming first rib portions of a first material on said substrate;

firing the formed first rib portions to produce post-fired, first rib portions of the higher height;

forming second rib portions of a second, contractable material and of the same height of the post-fired, higher height of said first rib patterns;

firing the second rib portions which, by thermally contracting, produce the second rib portions of the lower heights.

6. (ORIGINAL) The method for forming a rib pattern as claimed in claim 5, wherein the forming the second rib portions comprises:

forming a layer of the second, contractable material of the higher height;

forming a masking pattern, defining the second rib portions, on the layer of the second, contractable material; and

sandblasting the substrate to remove the second material layer except for the second rib portions defined by the masking pattern.

7. (ORIGINAL) The method for forming a rib pattern as claimed in claim 5, wherein the second, contractable material is a paste-like contractable material.

8. (ORIGINAL) The method for forming a rib pattern as claimed in claim 5, wherein said second material contains a white pigment.

9. (ORIGINAL) The method for forming a rib pattern as claimed in claim 5, wherein the rib portions of relatively higher heights comprise barrier rib portions.

10. (PREVIOUSLY PRESENTED) A method for forming a rib pattern, having rib portions of relatively lower and higher heights, on a substrate of a plasma display panel, the method comprising:

forming a first photosensitive rib material layer, having a thickness corresponding to the height of the lower height rib portions, on the substrate;

disposing thereon a first photolithographic mask having a pattern defining the lower

height rib portions, followed by exposure;

without development, superimposing on the first photosensitive rib material layer a second photosensitive rib material layer, a combined thickness of the first and second photosensitive rib material layers being substantially equal to the height of the higher height rib portions;

disposing on the second photosensitive rib material layer a second photolithographic mask having a pattern defining the higher height rib portions, followed by exposure; and

developing by removing the first and second photosensitive rib material layers, except for the lower and higher height rib portions defined respectively by the exposure with said photolithographic masks.

11. (PREVIOUSLY PRESENTED) The method for forming a rib pattern as claimed in claim 1, wherein the developing of the first and second photosensitive rib material layers is a single process.

12. (CANCELLED)

13. (CANCELLED)